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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
, 09/892,805	06/27/2001	Brian Lee	2001 P 11064US (8055-59)	3544
75	90 04/30/2003			
Infineon Technologies North America Corp. c/o Siemens Corporation Intellectual Property Department			EXAMINER	
			CYGAN, MICHAEL T	
186 Wood Avenue South Iselin, NJ 08830		ART UNIT	PAPER NUMBER	
<b>,</b>			2855	

DATE MAILED: 04/30/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

	I Americantical		nm-				
•	Application No.	ρplicant(s)	•				
Offic Action Summary	09/892,805	LEE ET AL.					
One Action Summary	Examiner	Art Unit					
The MAILING DATE of this communication app	Michael Cygan	2855	lalua a a				
Period for Reply	rears on the cover s	neet with the correspondence at	iaress				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).  Status	36(a). In no event, howeve y within the statutory minimu vill apply and will expire SIX , cause the application to be	r, may a reply be timely filed  um of thirty (30) days will be considered timel  (6) MONTHS from the mailing date of this c	y. ommunication.				
1) Responsive to communication(s) filed on	·						
2a) This action is <b>FINAL</b> . 2b) ⊠ Thi	is action is non-fina	1.					
3) Since this application is in condition for allowed in apparatoned with the processing under	ance except for form	nal matters, prosecution as to th	e merits is				
closed in accordance with the practice under a <b>Disposition of Claims</b>	Ex parte Quayle, 18	335 C.D. 11, 453 O.G. 213.					
4)⊠ Claim(s) <u>1-21</u> is/are pending in the application							
4a) Of the above claim(s) is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1-21</u> is/are rejected.							
7) Claim(s) is/are objected to.	7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or	r election requireme	ent.					
Application Papers	_						
9) The specification is objected to by the Examiner		biastad ta bu tha Evaminar					
10) The drawing(s) filed on <u>27 June 2001</u> is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.							
If approved, corrected drawings are required in reply to this Office action.							
12) The oath or declaration is objected to by the Examiner.							
Priority under 35 U.S.C. §§ 119 and 120							
13) Acknowledgment is made of a claim for foreign	priority under 35 U	.S.C. § 119(a)-(d) or (f).					
a) ☐ All b) ☐ Some * c) ☐ None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No							
<ul> <li>3. Copies of the certified copies of the prior application from the International Bur</li> <li>* See the attached detailed Office action for a list of the certified of the copies of the prior application.</li> </ul>	reau (PCT Rule 17.	2(a)).	Stage				
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).							
a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.							
Attachment(s)							
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s)	5) 🔲 No	terview Summary (PTO-413) Paper Not otice of Informal Patent Application (PTo her:					

Application/Control Number: 09/892,805

Art Unit: 2855

#### **DETAILED ACTION**

### Specification

The disclosure is objected to because of the following informalities: at page 9, line 5, "tip 24" is mentioned; however, this should be either "AFM 24" or "tip 26". Appropriate correction is required.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
  - 2. Claims 1-5, 9-11, 13, 16, 17, and 19 are rejected under 35 U.S.C. 102(b) as being anticipated by Yamanaka (US 6,006,593). Yamanaka discloses the claimed invention, a method of measuring physical properties of LSI (Large-Scale-Integrated Circuit) wafers with a cantilever comprising providing a feature (on a substrate such as a LSI wafer) having features of different elasticity, applying acoustic energy to the wafer by vibrating an AFM tip at an ultrasonic frequency, and scanning the sample wafer with the tip using optical deflection detection to determine the position and elasticity of surface features. See entire document, especially Figures 2,

Application/Control Number: 09/892,805

Art Unit: 2855

3, and 8; column 2 lines 14-29; column 3 lines 7-60; column 4 lines 40-57; column 5 lines 45-52; and column 8 lines 5-13.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
  - 3. Claims 7, 8, 14, 15, 20 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamanaka (US 6,006,593) in view of Mizutani (US 6,304,319 B1). Yamanaka teaches the claimed invention except for aligning the feature with a feature on a mask. Mizutani teaches the application of AFM measurement of surface features on substrates to aligning those features with marks on a mask using movement stages positioning substrate and mask; see column 1, lines 21-27; column 3, lines 41-55; and column 10, lines 46-50. It would have been obvious to one having ordinary skill in the art at the time the invention was made to use mask-substrate alignment steps as taught by Mizutani in the invention taught by Yamanaka to align LSI wafers with masks during processing, since Mizutani teaches that such mask-substrate alignment steps are "common" in the semiconductor manufacture art (see column 1, lines 21-

Application/Control Number: 09/892,805

Art Unit: 2855

27) and thus would provide a desirable application for feature recognition methods.

With respect to AFM resolution of less than 20 nm, it is notoriously well known in the AFM art that features less than 20 nm can be resolved, and it would therefore have been obvious to one having ordinary skill in the art at the time the invention was made to provide an AFM capable of 20 nm resolution.

4. Claims 6, 12, and 18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamanaka (US 6,006,593) in view of Weling (US 5,757,502). Yamanaka teaches the claimed invention except for pattern recognition. Weling teaches the use of optical pattern recognition to decipher the location of a surface feature on an integrated circuit chip in relation to the AFM; see column 7, lines 13-20 and Figure 10. It would have been obvious to one having ordinary skill in the art at the time the invention was made to use pattern recognition as taught by Weling in the invention taught by Yamanaka to locate measured surface features using optical pattern recognition, since this is taught to allow alignment of the AFM probe (which measures sub-micrometer features of a substrate) to absolute x and y coordinates and thus be related to macroscopic features of a substrate.

Art Unit: 2855

#### Conclusion

5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Quate (US 5,319,977) and Yamanaka (US 5,503,010) disclose ultrasonically vibrated tips detecting surface elasticity. Wafer positioning is disclosed by Kuroda (US 5,508,527), Shiraishi (US 6,538,740 B1), Mih (US 6,407,396 B1), and Ozaki (US 5,331,275).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael Cygan whose telephone number is 703-305-0846. The examiner can normally be reached on 8:30-6 M-Th, alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Edward Lefkowitz can be reached on 703-305-4816. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Michael Cygan April 28, 2003